

Max Marks: 80

## B.Tech I Year (R07) Supplementary Examinations, December 2010 APPLIED PHYSICS

(Electrical & Electronics Engineering, Electronics & Communication Engineering, Computer Science & Engineering, Electronics & Instrumentation Engineering, Biomedical Engineering, Information Technology, Electronics & Control Engineering, Electronics & Computer Engineering, Computer Science & Systems Engineering)

Time: 3 hours

Answer any FIVE questions All questions carry equal marks \*\*\*\*\*

- 1. (a) Define
  - i. lattice constant
  - ii. packing fraction and
  - iii. coordination number.
  - (b) Compare the unit cell properties of SC, BCC and FCC structures.
- 2. (a) What are Miller indices? Draw (111) and (110) planes in a cubic lattice.
  - (b) Explain Bragg's law of X-ray diffraction.
  - (c) The Bragg's angle for reflection from the (111) plane in a FCC crystal is  $19.2^{\circ}$  for an X-ray wavelength of 1.54 A.U. Compute the cube edge of the unit cell.
- 3. (a) Show that the wavelength of an electron accelerated by a potential difference 'V' volts, is  $\lambda = 1.227 \times 10^{-10} / \sqrt{V}$  m for non-relativistic case.
  - (b) Describe an experiment to establish the wave nature of electrons.
  - (c) Explain the difference between a matter wave and an electromagnetic wave.
- 4. (a) What are the salient features of the "free electron gas" model? Obtain Ohm's law based on it.
  - (b) Explain the concept of "effective mass".
- 5. (a) What is local field? Explain. Show that the local electrical field  $E_{loc}$  is given by  $E_{loc} = E\left(\frac{\varepsilon_r+2}{3}\right)$  where E is the applied electric field.
  - (b) An air-filled capacitor has a capacitance of 1.3 pf. The separation of the plates is halved and a dielectric is inserted between them. The new capacitance is 3.9 pf. Find the dielectric constant of the dielectric.
- 6. (a) Explain the effect of temperature and dopent on the Fermi level in a semiconductor.
  - (b) i. Find the conductivity of intrinsic silicon at 300 K. It is given that  $n_i$  at 300 K in silicon is  $1.5 \times 10^{16}/m^3$  and the mobilities of electrons and holes in silicon are 0.13  $m^2/V$ -s and 0.05  $m^2/V$ -s respectively.
    - ii. If donor type impurity is added to the extent of one impurity atom in  $10^8$  silicon atoms, find the conductivity.
    - iii. If acceptor type impurity is added to the extent of one impurity atom in  $10^8$  silicon atoms, find the conductivity.
- 7. (a) Explain the following:
  - i. Life time of an energy level.
  - ii. Optical pumping processes.
  - iii. Metastable states.
  - (b) Distinguish between spontaneous and stimulated emission processes of light.
  - (c) Discuss briefly the different methods of producing laser light.
- 8. (a) Distinguish between light propagation in
  - i. step index and
  - ii. graded index optical fibres.
  - (b) Discuss the various advantages of communication with optical fibres over the conventional coaxial cables.
  - (c) Calculate the refractive indices of core and cladding of an optical fibre with a numerical aperture of 0.33 and their fractional difference of refractive indices being 0.02.